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Title of Invention	Method for forming silicon dioxide film using siloxane	
Application Number :	10/782094	
Date :	2004-02-19	
First Named Applicant:	Mr. Park Jae-Eun	
Confirmation Number:	4756	
Attorney Docket Number:	SAM-0483	
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Submitted By:		Elec. Sign.
Mr. Anthony P. Onello Jr. Registered Number: 38,572	/Anthony P. Onello Jr./	Sign. Capacity Attorney

Documents being submitted:	Files
us-ids	SamsungFourEightyThreePartTwo-usidst.xml us-ids.dtd us-ids.xsl
Comments	
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